

	Typ e	Hi ts	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
1	BRS	1	high adj K near metal and metal near mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/10 18:17		0
2	BRS	4	high adj K with metal and metal with mask\$ and mask\$ with sacrificial	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:20		0
3	BRS	11	high adj K with metal and metal with mask\$ and mask\$ with sidewall with spacer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:20		0
4	BRS	16	high adj K with metal and metal with mask\$ and conformal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:29		0
5	BRS	39	high adj K with metal and metal with mask\$ and protect\$ and wet with etch\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:38		0
6	BRS	91	dielectric with metal and metal with mask\$ and wet near etch\$ with dielectric and (dry or plasma) near etch\$ with metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:55		0
7	BRS	6	6300202.URPN.	USPAT	2004/09/10 18:48		0
8	BRS	2	("5885877"   "6300202").PN.	USPAT	2004/09/10 18:50		0
9	BRS	30	5885877.URPN.	USPAT	2004/09/10 18:50		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error Rate
10	BRS	21	dielectric with metal and metal with mask\$ and wet near etch\$ with (high near K near dielectric or metal near oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 19:00		0
11	BRS	65	dielectric with metal and metal with mask\$ and mask with (sidewall near spacer or conformal\$ or protect\$ or sacrificial\$) and wet with etch\$ with (dielectric or metal near oxide) and etch\$ with metal and stack\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 17:51		0
12	BRS	10	high near k with dielectric and metal near gate and mask\$ with metal and sidewall with spacer with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 17:57		0
13	BRS	2	high near k with dielectric with metal and mask\$ near metal and sidewall with (spacer or protect\$) with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:00		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
14	BRS	17	dielectric with metal and mask\$ near metal and sidewall with (spacer or protect\$) with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:06		0
15	BRS	32	etch\$ with metal with stack and sidewall with (spacer or protect\$) with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:17		0
16	BRS	4	dielectric near substrate and metal near dielectric and mask\$ near metal and (sidewall or spacer or protect\$) near mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:21		0
17	BRS	96	(dielectric or oxide) with substrate and metal with (dielectric or oxide) and mask\$ with metal and (sidewall or spacer or protect\$) with mask\$ and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:24		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
18	BRS	24	(dielectric or oxide) with substrate and metal with (dielectric or oxide) and mask\$ with metal and (sidewall or spacer or protect\$) with mask\$ and high adj k and mask\$ with polysilicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:38		0
19	BRS	12	(dielectric or oxide) with substrate and metal with (dielectric or oxide) and mask\$ with metal and side\$6 with mask\$ and high adj k and mask\$ with polysilicon and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:43		0
20	BRS	45	gate near metal and mask\$ with metal and (cap\$6 or protect\$ or sacrificial) with mask\$ with side\$6 and mask\$ with polysilicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 19:21		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error Condition
21	BRS	2	gate near metal and mask\$ near (metal or gate) and high adj k with gate near dielectric and (cap\$6 or protect\$ or sacrificial) with mask\$ with side\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 19:25		0
22	BRS	3	gate near metal and high adj k with gate near dielectric and (cap\$6 or protect\$ or sacrificial) with mask\$ with side\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 19:26		0
23	BRS	34	gate near metal and high adj k with gate near dielectric and mask\$ with side\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 20:36		0
24	BRS	59	gate near metal and high adj k with gate near dielectric and mask\$ and work adj function	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:05		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
25	BRS	6	gate near metal and gate near dielectric and mask\$ near (metal or gate) and work adj function and (protect\$ or sacrificial or conformal) with metal with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:13		0
26	BRS	21	gate near metal with gate near dielectric and mask\$ near (metal or gate) and work adj function	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:20		0
27	BRS	3	etch\$ with gate near metal same mask\$ near (metal or gate) and work adj function and layer with (metal or gate) with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:27		0
28	BRS	11	etch\$ with gate near metal and mask\$ near (metal or gate) and work adj function and layer with (metal or gate) with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:28		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
29	BRS	1	etch\$ with gate near metal same mask\$ near (metal or gate) and work adj function and sacrificial with (metal or gate or mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:39		0
30	BRS	3	gate near metal same mask\$ near (metal or gate) and work adj function and sacrificial with (metal or gate or mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:32		0
31	BRS	6	etch\$ with gate near metal same mask\$ near (metal or gate) and sacrificial with (metal or gate or mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:33		0
32	BRS	17	etch\$ with gate near metal same mask\$ near (metal or gate) and protect\$ with (metal or gate) with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:34		0
33	BRS	1	etch\$ with gate same mask\$ near gate and sacrificial with metal with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:41		0
34	BRS	2	etch\$ and gate near stack\$ same mask\$ near gate and sacrificial with gate with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:45		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
35	BRS	1	etch\$ near gate same mask\$ near gate and work adj function and sacrificial with gate with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:47		0
36	BRS	3	etch\$ near gate same mask\$ near gate and sacrificial with gate with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:10		0
37	IS& R	2	("6063698").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:52		0
38	IS& R	2	("6184072").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:53		0
39	IS& R	2	("6420279").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:53		0
40	IS& R	2	("6475874").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:54		0
41	IS& R	2	("6514828").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:54		0
42	IS& R	2	("6544906").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:54		0
43	IS& R	2	("6617209").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:55		0
44	IS& R	2	("6620713").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:55		0
45	IS& R	2	("6689675").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:56		0
46	IS& R	2	("6696345").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:57		0

IBM\_TDB



	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error
47	IS&R	2	("6696327").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:57		0
48	IS&R	0	(2002/0197790).CLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:00		0
49	IS&R	2	("20020197790").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:01		0
50	IS&R	2	("20030032303").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:01		0
51	IS&R	2	("20030045080").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:01		0
52	BRS	11	mask\$ near side\$7 with sacrificial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:19		0
53	BRS	11	gate near stack\$ and mask\$ with sacrificial and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:20		0
54	BRS	11	gate near stack\$ and mask\$ with sacrificial and high adj k and metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:29		0
55	BRS	5	gate near stack\$ and mask\$ with prespacer and high adj k and metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:32		0
56	BRS	5	gate near stack\$ and mask\$ with prespacer and metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:33		0
57	BRS	15	gate near stack\$ and mask\$ with (sacrificial or prespacer) and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 14:18		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
58	BRS	3	gate near stack\$ and mask\$ with (sacrificial or prespacer) and gate near metal and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:47		0
59	BRS	108	mask\$ with (sacrificial or prespacer) and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:48		0
60	BRS	14	mask\$ with (sacrificial or prespacer) and gate near metal and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 13:49		0
61	BRS	3	mask\$ near metal and gate near metal and high adj k and work adj function	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 13:53		0
62	BRS	30	mask\$ and gate near metal and high adj k and work adj function and gate near stack\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 13:54		0
63	BRS	19	gate near stack\$ and mask\$ with (sacrificial or prespacer or liner or lining) and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 14:19		0

	Type	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
1	BRS	1	high adj K near metal and metal near mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:17		0
2	BRS	4	high adj K with metal and metal with mask\$ and mask\$ with sacrificial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:20		0
3	BRS	11	high adj K with metal and metal with mask\$ and mask\$ with sidewall with spacer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:20		0
4	BRS	16	high adj K with metal and metal with mask\$ and conformal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:29		0
5	BRS	39	high adj K with metal and metal with mask\$ and protect\$ and wet with etch\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:38		0
6	BRS	91	dielectric with metal and metal with mask\$ and wet near etch\$ with dielectric and (dry or plasma) near etch\$ with metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 18:55		0
7	BRS	6	6300202.URPN.	USPAT	2004/09/10 18:48		0
8	BRS	2	("5885877"   "6300202").PN.	USPAT	2004/09/10 18:50		0
9	BRS	30	5885877.URPN.	USPAT	2004/09/10 18:50		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
10	BRS	21	dielectric with metal and metal with mask\$ and wet near etch\$ with (high near K near dielectric or metal near oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/10 19:00		0
11	BRS	65	dielectric with metal and metal with mask\$ and mask with (sidewall near spacer or conformal\$ or protect\$ or sacrificial\$) and wet with etch\$ with (dielectric or metal near oxide) and etch\$ with metal and stack\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 17:51		0
12	BRS	10	high near k with dielectric and metal near gate and mask\$ with metal and sidewall with spacer with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 17:57		0
13	BRS	2	high near k with dielectric with metal and mask\$ near metal and sidewall with (spacer or protect\$) with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:00		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
14	BRS	17	dielectric with metal and mask\$ near metal and sidewall with (spacer or protect\$) with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:06		0
15	BRS	32	etch\$ with metal with stack and sidewall with (spacer or protect\$) with mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:17		0
16	BRS	4	dielectric near substrate and metal near dielectric and mask\$ near metal and (sidewall or spacer or protect\$) near mask\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:21		0
17	BRS	96	(dielectric or oxide) with substrate and metal with (dielectric or oxide) and mask\$ with metal and (sidewall or spacer or protect\$) with mask\$ and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:24		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
18	BRS	24	(dielectric or oxide) with substrate and metal with (dielectric or oxide) and mask\$ with metal and (sidewall or spacer or protect\$) with mask\$ and high adj k and mask\$ with polysilicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:38		0
19	BRS	12	(dielectric or oxide) with substrate and metal with (dielectric or oxide) and mask\$ with metal and side\$6 with mask\$ and high adj k and mask\$ with polysilicon and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 18:43		0
20	BRS	45	gate near metal and mask\$ with metal and (cap\$6 or protect\$ or sacrificial) with mask\$ with side\$6 and mask\$ with polysilicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 19:21		0

	Typ e	Hi ts	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
21	BRS	2	gate near metal and mask\$ near (metal or gate) and high adj k with gate near dielectric and (cap\$6 or protect\$ or sacrificial) with mask\$ with side\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 19:25		0
22	BRS	3	gate near metal and high adj k with gate near dielectric and (cap\$6 or protect\$ or sacrificial) with mask\$ with side\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 19:26		0
23	BRS	34	gate near metal and high adj k with gate near dielectric and mask\$ with side\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 20:36		0
24	BRS	59	gate near metal and high adj k with gate near dielectric and mask\$ and work adj function	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:05		0
25	BRS	6	gate near metal and gate near dielectric and mask\$ near (metal or gate) and work adj function and (protect\$ or sacrificial or conformal) with metal with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:13		0

	Type	Hits	Search Text	DBs	Time Stamp	C	o	r	d	E
	e	t				m	m	r	e	r
						e	n	s	i	r
						s	t		t	r
							i		i	r
							o			r
										s
26	BRS	21	gate near metal with gate near dielectric and mask\$ near (metal or gate) and work adj function	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:20					0
27	BRS	3	etch\$ with gate near metal same mask\$ near (metal or gate) and work adj function and layer with (metal or gate) with	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:27					0
28	BRS	11	mask\$ with gate near metal and mask\$ near (metal or gate) and work adj function and layer with (metal or gate) with	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:28					0
29	BRS	1	mask\$ with gate near metal same mask\$ near (metal or gate) and work adj function and sacrificial with (metal or gate or mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:39					0
30	BRS	3	gate near metal same mask\$ near (metal or gate) and work adj function and sacrificial with (metal or gate or mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:32					0



	Type	Hits	Search Text	DBs	Time Stamp	Comments	Errors
39	IS&R	2	("6420279").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:53		0
40	IS&R	2	("6475874").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:54		0
41	IS&R	2	("6514828").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:54		0
42	IS&R	2	("6544906").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:54		0
43	IS&R	2	("6617209").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:55		0
44	IS&R	2	("6620713").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:55		0
45	IS&R	2	("6689675").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:56		0
46	IS&R	2	("6696345").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:57		0
47	IS&R	2	("6696327").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:57		0
48	IS&R	0	(2002/0197790).CC LS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:00		0
49	IS&R	2	("20020197790").P N.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:01		0
50	IS&R	2	("20030032303").P N.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:01		0
51	IS&R	2	("20030045080").P N.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:01		0

	Typ e	Hi ts	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
52	BRS	11	mask\$ near side\$7 with sacrificial	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:19		0
53	BRS	11	gate near stack\$ and mask\$ with sacrificial and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:20		0
54	BRS	11	gate near stack\$ and mask\$ with sacrificial and high adj k and metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:29		0
55	BRS	5	gate near stack\$ and mask\$ with prespacer and high adj k and metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:32		0
56	BRS	5	gate near stack\$ and mask\$ with prespacer and metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:33		0
57	BRS	15	gate near stack\$ and mask\$ with (sacrificial or prespacer) and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 14:18		0
58	BRS	3	gate near stack\$ and mask\$ with (sacrificial or prespacer) and gate near metal and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:47		0
59	BRS	10 8	mask\$ with (sacrificial or prespacer) and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 12:48		0
60	BRS	14	mask\$ with (sacrificial or prespacer) and gate near metal and high adj k	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 13:49		0

	Type	Hits	Search Text	DBs	Time Stamp	Comments	Error Count
61	BRS	3	mask\$ near metal and gate near metal and high adj k and work adj function	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 13:53		0
62	BRS	30	mask\$ and gate near metal and high adj k and work adj function and gate near stack\$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 13:54		0
63	BRS	19	gate near stack\$ and mask\$ with (sacrificial or prespacer or liner or lining) and gate near metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/13 14:19		0

	Type	Hits	Search Text	DBs	Time Stamp	C	E	E
						o	r	r
						m	r	r
						e	e	r
						n	n	s
						s	s	i
						t	t	t
						i	i	i
						o	o	o
31	BRS	6	etch\$ with gate near metal same mask\$ near (metal or gate) and sacrificial with (metal or gate or mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:33			0
32	BRS	17	etch\$ with gate near metal same mask\$ near (metal or gate) and protect\$ with (metal or gate) with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:34			0
33	BRS	1	etch\$ with gate same mask\$ near gate and sacrificial with metal with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:41			0
34	BRS	2	etch\$ and gate near stack\$ same mask\$ near gate and sacrificial with gate with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:45			0
35	BRS	1	etch\$ near gate same mask\$ near gate and work adj function and sacrificial with gate with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:47			0
36	BRS	3	etch\$ near gate same mask\$ near gate and sacrificial with gate with mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 22:10			0
37	IS& R	2	("6063698").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:52			0
38	IS& R	2	("6184072").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/11 21:53			0